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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of

Clevenger et al.

Serial No.: 09/772,920

Group Art Unit: 2825

Filed: January 31, 2001

Examiner: Keshavan, Belur V.

For: METHOD FOR PRODUCING DUAL DAMASCENE INTERCONNECTIONS AND STRUCTURE PRODUCED THEREBY

Honorable Commissioner of Patents
Washington, D.C. 20231

AMENDMENT UNDER 37 C.F.R. § 1.111

Sir:

In response to the Office Action dated October 23, 2002, please amend the above-identified application as follows:

IN THE CLAIMS:

Please cancel claim 17 without prejudice or disclaimer.

Please amend claims 6, 10, and 15, as follows:

6. (Amended) The method of claim 5, wherein said dielectric comprises one of tetraethylorthosilicate (TEOS) oxide, silane oxide, and another low K polymer dielectric.

10. (Amended) The method of claim 5, wherein a thickness of the conducting material is adjusted so as to completely fill the slot. — *New alternative* *Drawing (A) & (B)* *metal*

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